

ALD NanoSolutions, Inc.

Precision NanoCoating for NanoParticles

July 2005 The University of Colorado has been awarded U.S. Patent number 6,913,827 “Nanocoated primary particles and method for their manufacture,” which has been exclusively licensed to ALD NanoSolutions, Inc. The patent includes composition of matter and process claims on nanocoated micron and submicron particles. Four patents covering the platform Particle ALD™ coating technology have been issued.

Previous patents issued are: U.S. Patent 6,613,383 entitled: “Atomic Layer Controlled Deposition on Particle Surfaces;” U.S. Patent 6,713,177 entitled “Insulating and Functionalizing Fine Metal Particles With Conformal Ultrathin Films;” and U.S. Patent Application No. 60/306,521 entitled “Method for the Deposition of an Inorganic Film on an Organic Polymer Surface Using Atomic Layer Deposition Techniques.”

About ALD NanoSolutions

ALD NanoSolutions, Inc. was founded in 2002 by P. Michael Masterson, Dr. Karen Buechler, and University of Colorado Professors Dr. Steven George and Dr. Alan Weimer. The company's proprietary technology is based on atomic layer deposition (ALD) coating chemistry and fluidized bed processing methods developed by Dr. George and Dr. Weimer for depositing ultrathin films on particulate and polymeric surfaces. The company is focused on commercializing its nanocoating processes, called Particle ALD™ and Polymer ALD™, and is targeting collaborative research agreements with domain partners for the discovery and validation of innovative composite materials in selected industries. Particle ALD™ has been named one of R & D magazine's top 100 innovations for 2004.